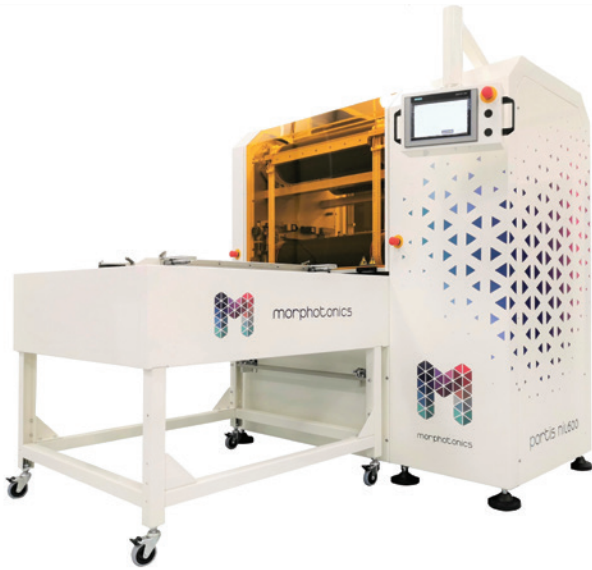


Portis NIL600

Introducing the ultimate in flexibility & convenience



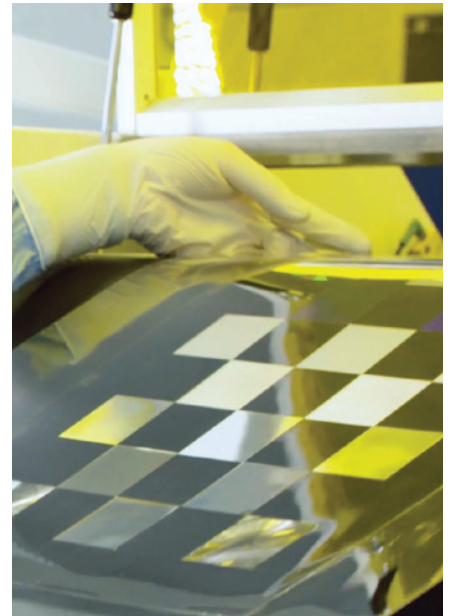
We understand the importance of R&D especially when you are still investigating the specifications for your final product. Portis 600 is a modular Roll-to-Plate (R2P) nanoimprint equipment designed for R&D, process development, and pilot production, with large-area capability.

This innovative machine allows to easily change flex stamps and seamlessly adjust properties like speed, pressure, gap, and UV settings. To meet customers' R&D and pilot production needs, the Portis NIL600 is compatible with both the Portis Primer P1100 and Coater C1100, as well as various pre-treatment and post-process options.

Substrate Size	Up to Gen3 (650 x 550 mm ²)
Substrate Thickness	0.5 – 10 mm
Substrate materials	Rigid & flexible (glass, polymer, metal)
Structures	From 50 nm up to 500 µm
TAKT time	<5 min possible



Watch our Portis equipment in action



Any optics, any display, any size

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MORPHOTONICS
Nanoimprint technologies